“Optimization of Carbon Nanotube Field Emission Arrays”
Overview

- Motivation
- CNT Array Models
- Simulation Results
- Conclusions
Motivation

- Carbon nanotubes as emitters
  - Narrow diameters
  - High aspect ratios
  - Good conductivity
  - High temperature stability
  - Structural strength

- CNT emission is due to high localized electric field that forms at small diameter tips.
Motivation

- Triode (gated) Devices
  - Lower extraction voltage
  - Simpler control
  - Reduce screening effects

- Maximize field emission by optimizing array geometries within available fabrication processes to maximize the electric field strength at the CNT emitters.
• 2-D model of base CNT array
  • CNTs with 50 nm diameter and 50 nm spacing
  • Array pitch of 1 µm
  • Array elements of 1 µm
  • Element shape (square and round)
  • Dielectric thickness of 2 µm
CNT Array Models

- Optimized electric field strength by varying:
  - CNT spacing
  - Array pitch
  - Array element dimensions
  - Element shape
  - Dielectric thickness

- Simulations used both 2D and 3D models
Simulation Results

- CNT spacing within array element
  - Single CNT
  - 200 nm
  - 50 nm

- Single CNT
  - Strongest E-field
  - Complete electrostatic field penetration
Simulation Results

• 200 nm CNT separation
  • 3 CNTs
  • Significantly reduced penetration
  • 42% Reduction in center CNT E-field
Simulation Results

- 50 nm CNT separation
  - 9 CNTs (center 5 shown)
  - Significantly reduced penetration
  - 60% Reduction in center CNT E-field

- Screening effects are significant within array elements
Simulation Results

• **Element pitch and dimension**
  - Potential increase in field emission current density through increase in total number of elements with stronger E-fields
  - Element dimensions (green) of 1 µm and 0.5 µm simulated with pitches (red) of 3 µm, 2 µm, 1 µm, and 0.5 µm
Simulation Results

Electric Field (V/µm)

CNTs Across Gate (5 is center CNT)

- 1um gate 3um pitch
- 1um gate 2um pitch
- 1um gate 1um pitch
- 1um gate 0.5um pitch
- 0.5um gate 3um pitch
- 0.5um gate 2um pitch
- 0.5um gate 1um pitch
- 0.5um gate 0.5um pitch
Simulation Results

- Decreasing element dimensions increases E-field
  - Reduction from 1 µm to 0.5 µm increased E-field at center from 3.3 V/µm to 6.1 V/µm
- Pitch has little effect on E-field strength
  - Decreasing pitch from 3 µm to 0.5 µm had no effect on the E-field at the center of the element
  - ~4% drop at edge CNTs
- Screening effects dominate center of elements
Simulation Results

- 3D simulations also showed no difference between
  - a) 0.5 µm pitch
  - b) 1 µm pitch

E-field strength at CNT tips across center element of a 3x3 array
Simulation Results

- 3D simulations resulted in a greater increase in E-field with a reduction in element dimension
  - a) 1 µm element diameter: E-field at center 5.3 V/µm
  - b) 0.5 µm element diameter: E-field at center 14.7 V/µm

E-field strength at CNT tips across center element of a 3x3 array
Simulation Results

- Square elements also showed greater increase in E-field
  - a) 1 µm element: E-field at center 7.8 V/µm
  - b) 0.5 µm element: E-field at center 17.7 V/µm
- Square elements had stronger E-field at element center

E-field strength at CNT tips across center element of a 3x3 array
Simulation Results

- Reduction in dielectric layer had little effect on the E-field
  - a) 1 µm dielectric layer: E-field at center 14.7 V/µm
  - b) 2 µm dielectric layer: E-field at center 15.2 V/µm
- 0.5 µm layer resulted in a 10% reduction of center E-field

E-field strength at CNT tips across center element of a 3x3 array
Conclusions

- Electrostatic screening between CNTs dominates the E-field strength within an element
- Pitch can be reduced to increase array current densities
- Smaller element dimensions significantly increases the E-field magnitude across an element
  - Also increases the total number of elements in the array
- Square elements had stronger E-field at the center of the element
- Large reductions in dielectric thickness resulted in only small decreases in E-field magnitude
Conclusions

- Optimized CNT field emission array design based on available fabrication capabilities
  - Circular elements with 0.5 µm diameter
  - 0.5 µm pitch
  - 1 µm thick dielectric layer
Questions

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